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U6090-3

PATENT APPLICATION

1732 Ihr

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
	;	Examiner: M. Vargot
Stephen Y. Chou)	Group Art Unit: 1732
Application No.: 10/046,594	;	Group Art Offic. 1732
•	:	
Filed: October 29, 2001)	
For: IMPROVED RELEASE SURFACES,	,	
PARTICULARLY FOR USE IN	:	
NANOIMPRINT LITHOGRAPHY)	December 2, 2004
Mail Stop Amendment		
Commissioner for Patents		
P.O. Box 1450		
Alexandria, VA 22313-1450		

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed PTO-1449. Copies of the listed documents are also enclosed. It is respectfully requested that the PTO-1449 form be initialed and returned, indicating that the cited references have been considered.

I hereby certify that this correspondence is being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on

December 2, 2004

Date of Deposit

Daniel D. Sierchio (Reg. No. 53,591

Name

December 2, 2004

Date of Signature

December 2, 2004

Date of Signature

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FEES

The Commissioner is authorized to charge \$180.00 to Deposit Account 501358 to cover the required Information Disclosure Statement fee under 37 C.F.R. 1.17(p). Any deficiency in or overpayment of the fee may be charged or credited to this Deposit Account. A duplicate of this submission is attached for accounting purposes.

CONCLUSION

Applicants' undersigned attorney may be reached by telephone at (973) 597-2500. All correspondence should continue to be directed to our address listed below.

Respectfully submitted,

DANIEL D. SIERCHIO Attorney for Applicant

Registration No. 53,591

DOCKET ADMINISTRATOR Lowenstein Sandler PC 65 Livingston Avenue Roseland, NJ 07068



Docket Number (Optional) Application Number U6090-3 10/046,594 Applicant(s) INFORMATION DISCLOSURE CITATION Stephen Y. Chou (Use several sheets if necessary) Filing Date Group Art Unit 10/29/01 1732 **U.S. PATENT DOCUMENTS** EXAMINER FILING DATE REF DOCUMENT NUMBER DATE INITIAL NAME CLASS SUBCLASS APPROPRIATE **FOREIGN PATENT DOCUMENTS** TRANSLATION **EXAMINER** DOCUMENT NUMBER DATE NAME CLASS SUBCLASS INITIAL OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) K. Pfeiffer, et al., "Reactive Polymers- a Route to Nanoimprint Lithography at Low Temperatures", June 2003, Pages 203-210 K. Pfeiffer, et al., "A comparison of thermally and photochemically cross-linked polymers for nanoimprinting", Microelectronic Engineering, Vol. 67-68, 2003. Pages 266-273 H. Schulz, et al., "Low-Temperature Wafer-Scale 'WARM' Embossing for Mix & Match with UV-Lithography", Proceedings of SPIE Vol. 4688, 2002, Pages 223-231 D.J. Resnick, et al., "Imprint lithography for integrated circuit fabrication", J. Vac. Sci. Technol., B 21(6), Nov/Dec 2003, Pages 2624-2631 C. Gourgon, et al., "Influence of pattern density in nanoimprint lithography", J. Vac. Sci. Technol., B 21(1), Jan/Feb 2003, Pages 98-105 Dahl-Young Khang, et al., "Room-temperature imprint lithography by solvent vapor treatment", Applied Physics Letters, Vol. 76, No. 7, February 14, 2000, Pages 870-872 A. Lebib, et al., "Room-temperature and low-pressure nanoimprint lithography", Microelectronic Engineering, Vol. 61-62, 2002, Pages 371-377 K. Pfeiffer, et al., "Suitability of new polymer materials with adjustable glass temperature for nano-imprinting", Microelectronic Engineering, Vol. 46, 1999, Pages 431-434

Examiner Signature

Date Considered

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-A820 (also form PTO-1449)